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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

:

Hiroyuki YANO et al

: GROUP ART UNIT: 1765

SERIAL NO.: 09/531,163

: EXAMINER: Duy Vu DEO

FILED: March 17, 2000

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FOR: AQUEOUS DISPERSION, AQUEOUS DISPERSION FOR CHEMICAL  
MECHANICAL POLISHING USED FOR MANUFACTURE OF  
SEMICONDUCTOR DEVICES, METHOD FOR MANUFACTURE OF  
SEMICONDUCTOR DEVICES, AND METHOD FOR FORMATION OF  
EMBEDDED WIRING

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

RECEIVED  
MAY 0-7 2002  
TC 1700

SIR:

Responsive to the Advisory Action of April 16, 2002 Applicants respectfully request reconsideration of above-identified application in view of a Request for Reconsideration submitted with the following amendment and remarks.

IN THE CLAIMS

Please amend the claims as shown in the marked-up copy following this amendment to read as follows.

44. (Amended) A dispersion comprising polymer particles, inorganic particles and water, wherein the zeta potential of said polymer particles and the zeta potential of said inorganic particles are of opposite signs, and said polymer particles and said inorganic particles are electrostatically bonded to form composite particles, and

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